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Polymerization of Fluoroalkyl Polyhedral Oligomeric Silsesquioxane (F-POSS) Macromers

Sean M. Ramirez,¹ Yvonne Diaz,² Timothy S. Haddad,¹ and Joseph M. Mabry²

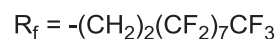
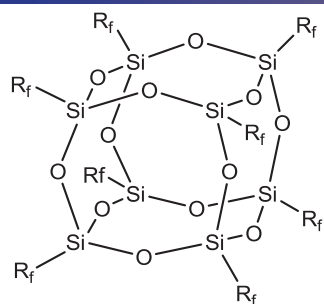
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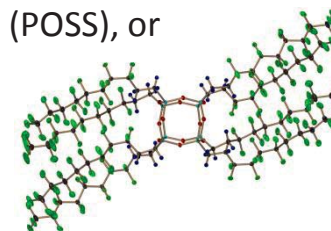


Introduction to F-POSS



(1,1,2,2-tetrahydroperfluorodecyl)₈Si₈O₁₂ Polyhedral Oligomeric Silsesquioxane (POSS), or fluorodecyl POSS

- hybrid organic-inorganic structure
- well-defined polyhedral architecture
- long-chain fluoroalkyl substituents on periphery of cage



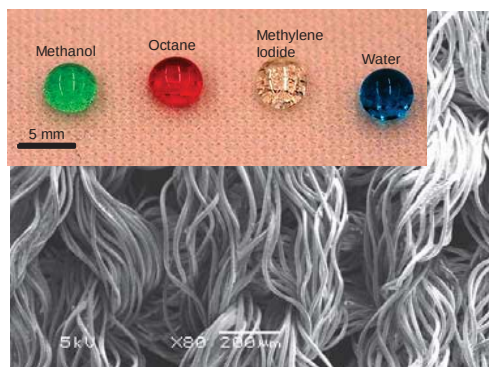
Due to its unique structure, fluorodecyl POSS has one of the lowest surface energies of any crystalline solid currently known

- | | |
|-----------------------------|------------|
| - fluorodecyl POSS | 9.3 mN/m |
| - polytetrafluoroethylene | 18-20 mN/m |
| - CF ₃ monolayer | 6.7 mN/m |

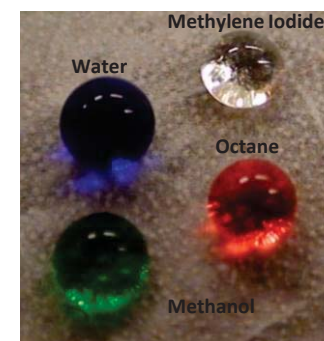
Low surface energy and other unique properties of fluorodecyl POSS has enabled the development of various types of tunable non-wetting polymeric surfaces



Superhydrophobic/oleophilic dip-coated fabric
Tuteja *et al*, Science, **2007**, 318, 1618



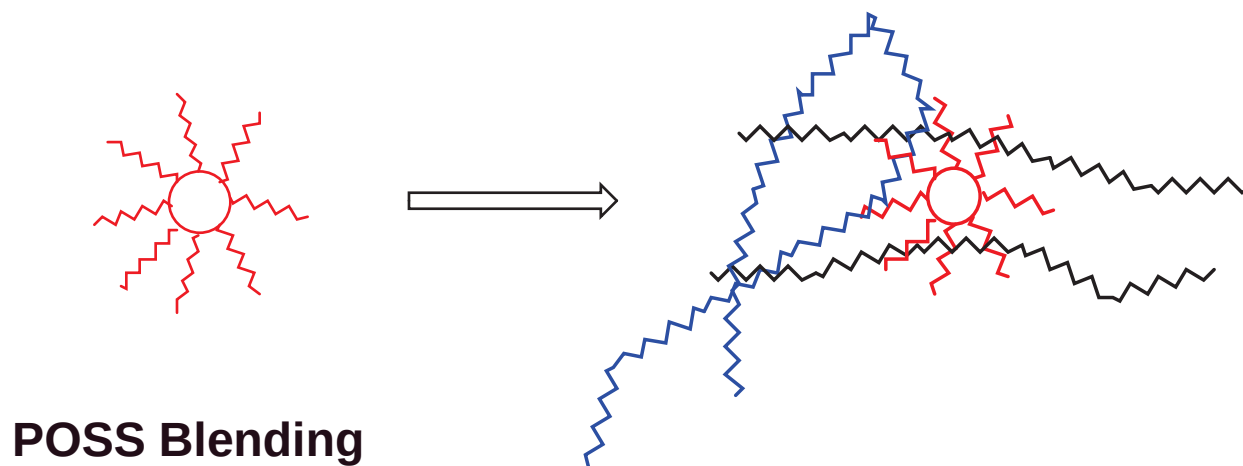
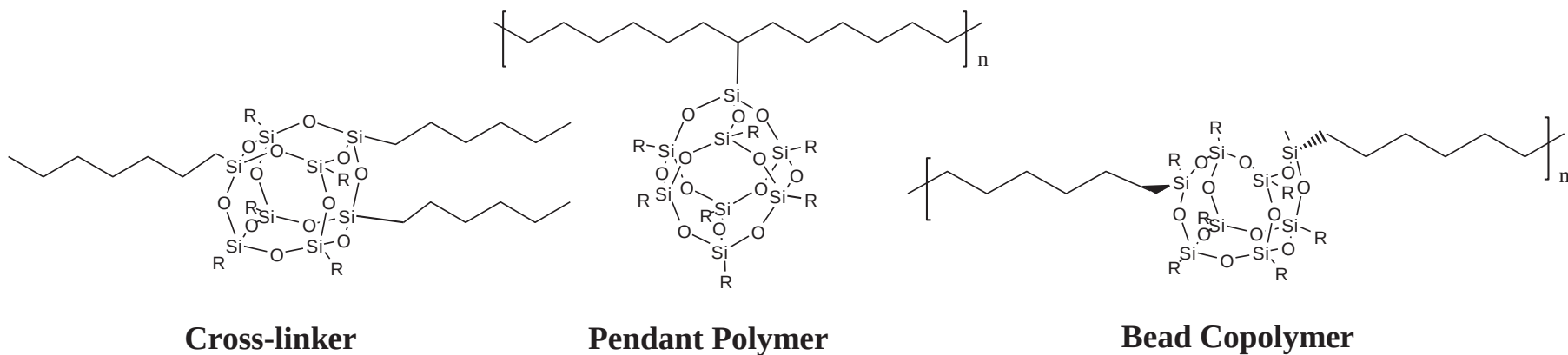
Superamphiphobic dip-coated fabric
Choi *et al*, Adv Mater, **2009**, 21, 2190



Superamphiphobic electrospun surfaces
Tuteja *et al*, PNAS, **2008**, 105, 18200



POSS Incorporation in Polymers



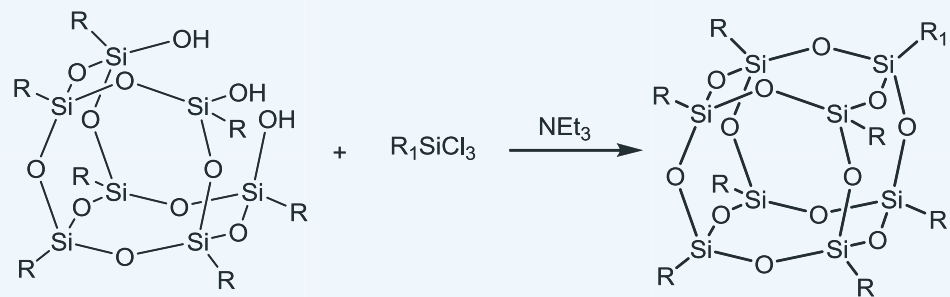
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Cordes, D. B.; Lickiss, P. D.; Rataboul, F., *Chem. Rev.* 2010, *110* (4), 2081-2173. Phillips, S. H.; Haddad, T. S.; Tomczak, S. J., *Curr. Opin. Solid State Mater. Sci.* 2004, *8*, 21-29 Iacono, S. T.; Buddy, S. M.; Mabry, J. M.; Jr., D. W. S., *Polymer* 2007, *48*, 4637-4645. Koh, K; et. al., *Macromolecules* 2005, *38*, 1264-1270.



Functional F-POSS (Open-Caged)

- Close-caged structures are accessible and have proven versatile in polymer composites
 - Limitations
 - Solubility, mechanical robustness (surface abrasion), no sites for functionality
- Open-caged structures would allow for functionalization of F-POSS
 - Open door for use a *building block* material for *low surface energy materials*
- Applications
 - Mechanical robust superhydrophobic/oleophobic/omniphobic surfaces
 - Via covalently attached F-POSS to substrate (surface, nanoparticle, polymer matrix)
 - Effects on polymer composite properties
 - Wetting, phase behavior, solubility, etc....



- Open cages lead to functional POSS structures
- Reactions are simple
- High yields typically reported



Methods to Produce Incompletely Condensed Silsesquioxanes



- Bottom-up approach
 - Acid or base mediated from RSiCl_3 or RSi(OR)_3
 - Condensation reaction
 - Balance of stoichiometry, temperature, reaction time, patience, and luck
 - Stopping POSS synthesis early, before cages closes
 - More common approach
- Top-down Approach
 - Strong acid or base mediated
 - Starting from a POSS cage
 - Conversion of Si-O-Si bonds to Si-O⁽⁻⁾ C⁽⁺⁾ or Si-OH bonds
 - Opening up POSS cage

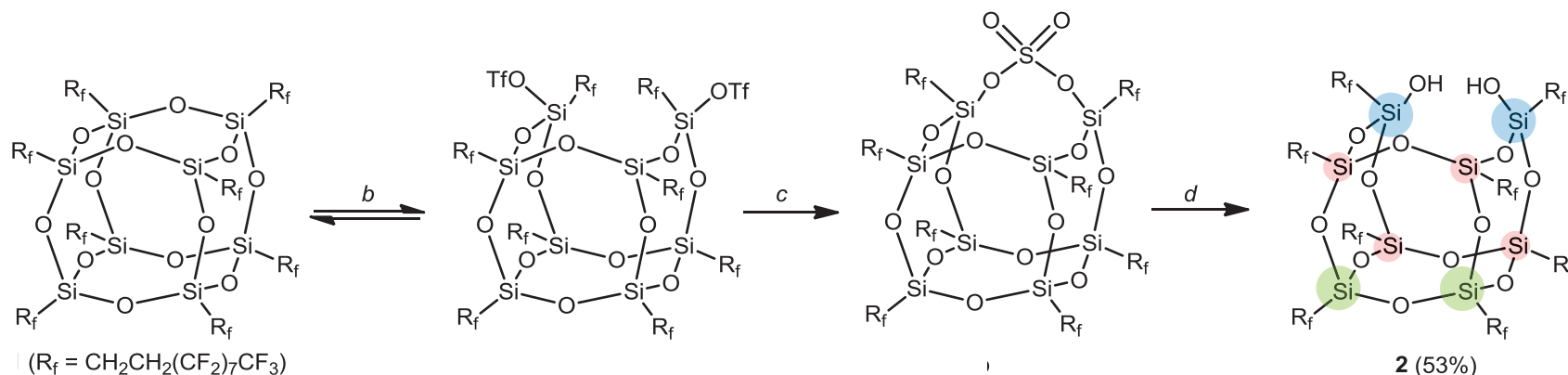
Which method can be applied to long-chain F-POSS?

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Feher, F. J.; Terroba, R.; Ziller, J. W. *Chemical Communications* **1999**, 2309. Feher, F. J.; Newman D.A.; Walzer, J.M., *J. Am. Chem. Soc.*, **1989**, 111, 1741. Feher, F. J.; Soulivong, D.; Nguyen, F.; Ziller, J. W. *Angew.Chem. Inter. Ed.* **1998**, 37, 2663. Feher, F. J.; Soulivong, D.; Nguyen, F. *Chem. Commun.* **1998**, 1279.

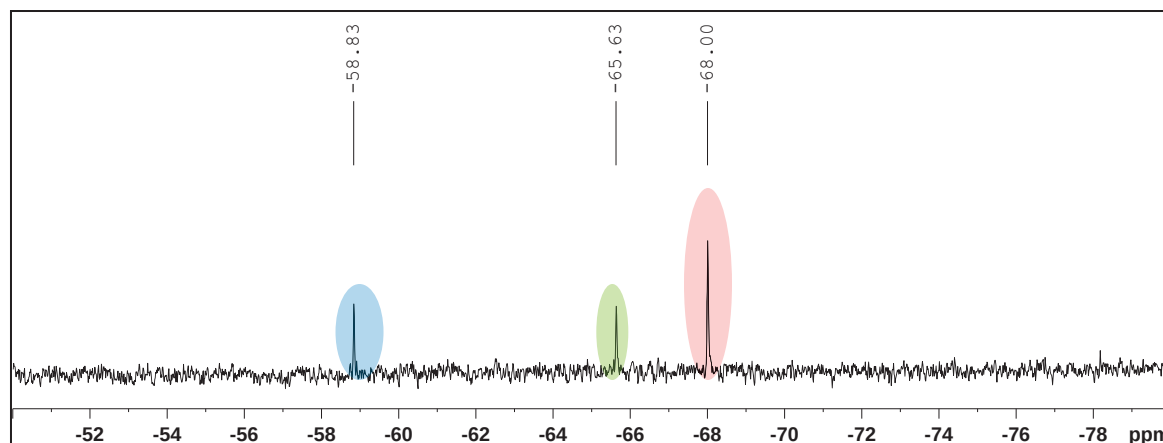


Incompletely Condensed Silsesquioxane



^aConditions: All reactions were performed in C_6F_6 at 25 °C. ^b $\text{CF}_3\text{SO}_3\text{H}$, 75 mins. ^c $\text{NBut}_4\text{HSO}_4$, 30 mins, ^d $(\text{CF}_3)_2\text{CH}_2\text{OH}/\text{H}_2\text{O}$ (10:1), 12 hrs.

²⁹Si NMR in C_6F_6 of disilanol F-POSS



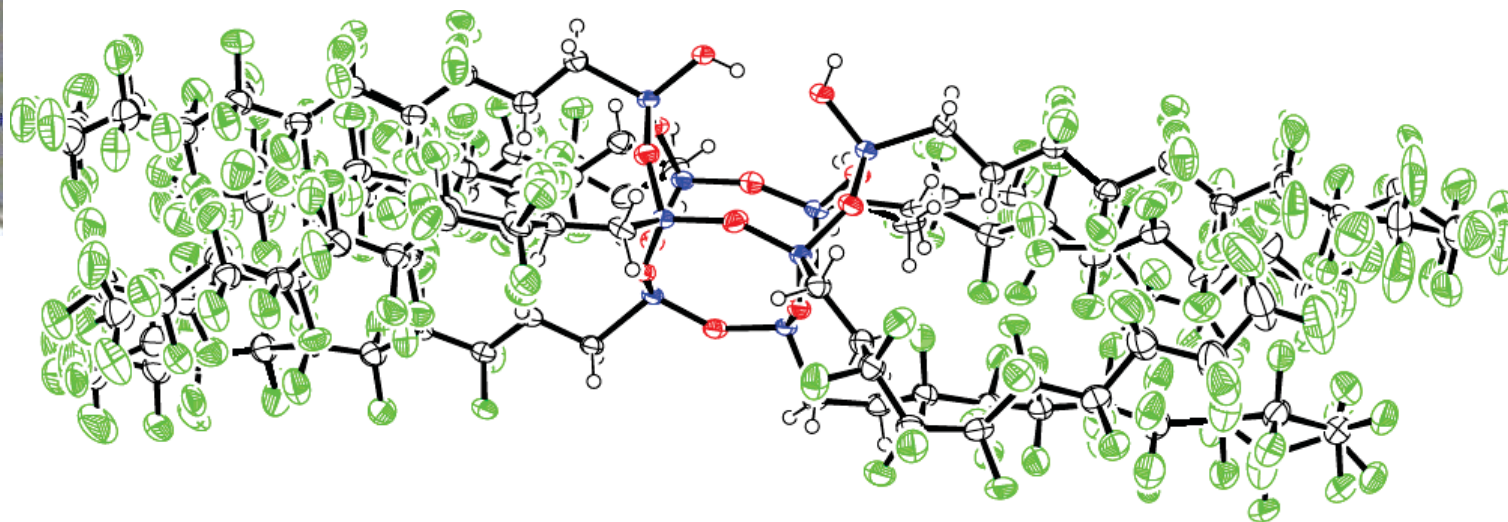
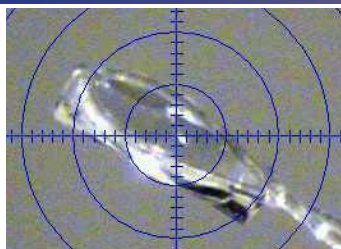
- Incompletely condensed silsesquioxane synthesis yields a disilanol capable of functionalization with dichlorosilanes.

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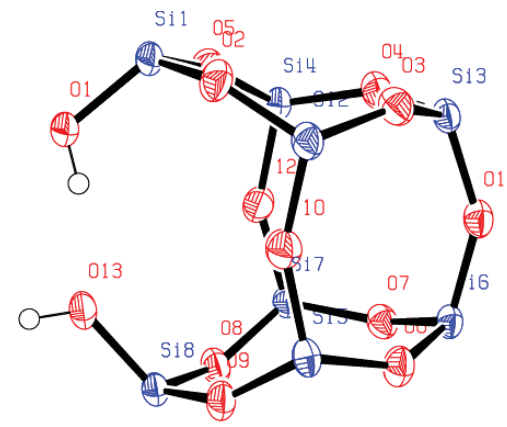
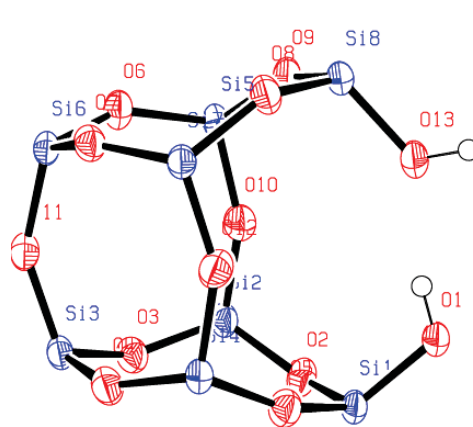
Ramirez, S. M.; Diaz, Y. J.; Campos, R.; Haddad, T. S.; Mabry, J. M. ACS Symposium Series" Advances in Fluorine Containing Polymers 2012 1106, 95-109.
Ramirez, S. M.; Diaz, Y. J.; Campos, R.; Stone, R.T.; Haddad, T.S.; Mabry, J.M., J. Am. Chem. Soc., 2011, 133, 20084.



X-Ray Crystal Structure of Disilanol



- Crystal structure is dimeric via intra- and intermolecular hydrogen bonding between silanols.
- M_r = monoclinic, space group $P2(1)/c$, $a=11.84(10)$ Å, $b=57.11(6)$ Å, $c=19.06(2)$ Å, $\alpha=90.00^\circ$, $\beta=92.21(10)^\circ$, $\gamma=90.00^\circ$, $V=12878(2)$ Å³



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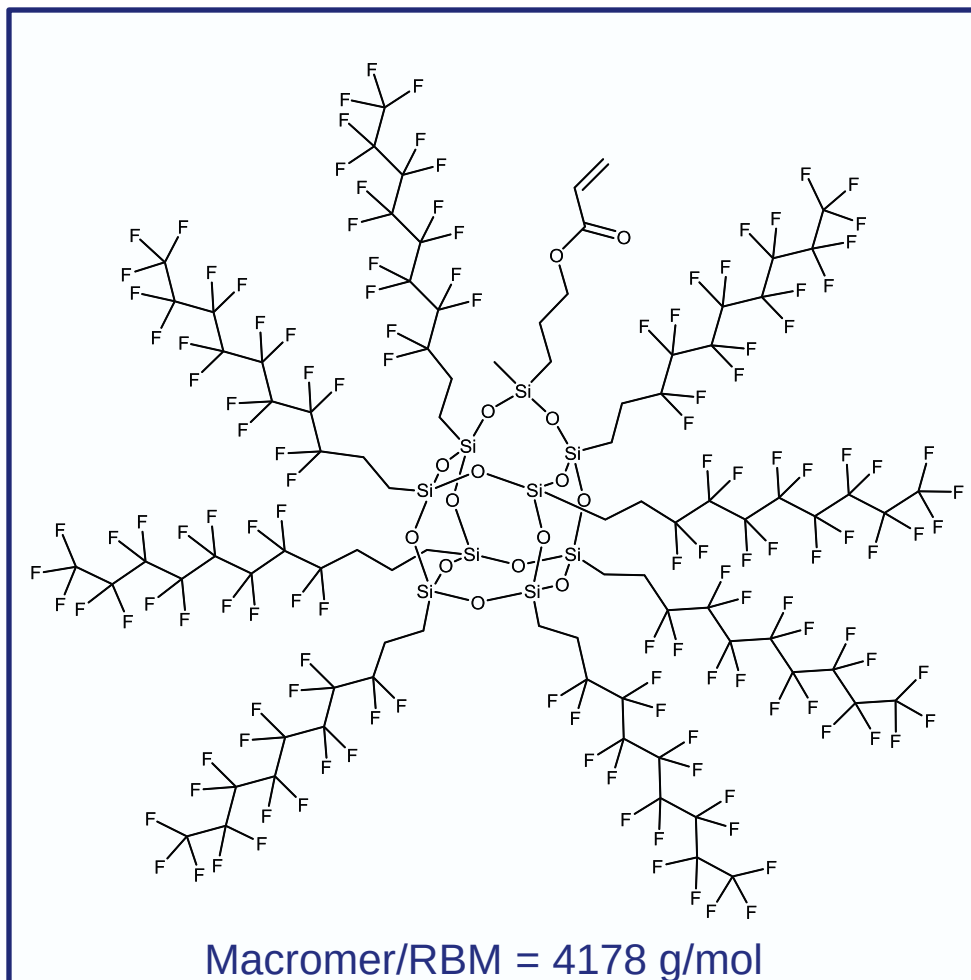


Edge Capping Reactions



$R = \text{CH}_2\text{CH}_2(\text{CF}_2)_7\text{CF}_3$
 $R_1 = \text{alkyl or aromatic}$
 $R_2 = \text{alkyl or aromatic}$

- Edge capping reactions typically have 40-90% yield
- Main side product is starting material (recycled)
- Disilanol can revert back to closed cage during reaction



Macromer/RBM = 4178 g/mol

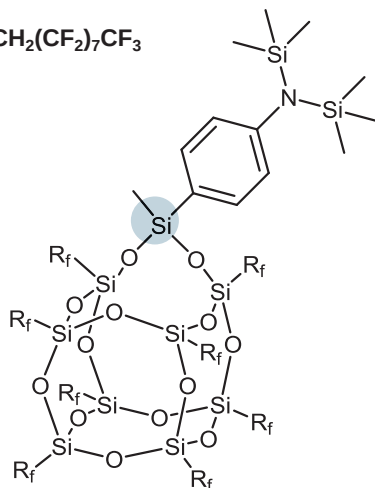
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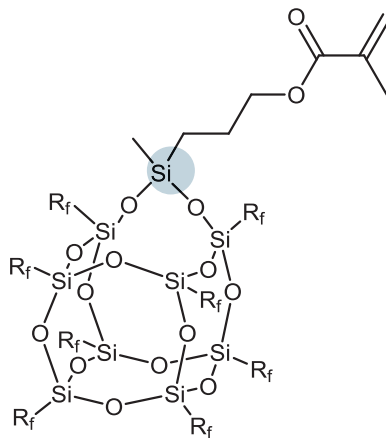


^{29}Si NMR of F-POSS Structures

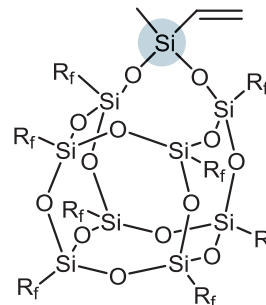
$\text{R} = \text{CH}_2\text{CH}_2(\text{CF}_2)_7\text{CF}_3$



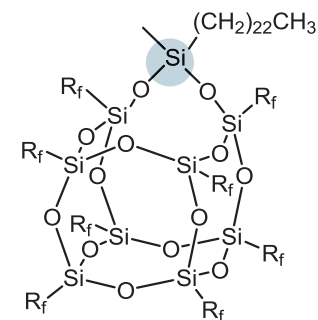
-29.5 ppm



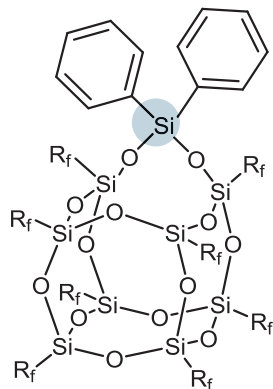
-17.8 ppm



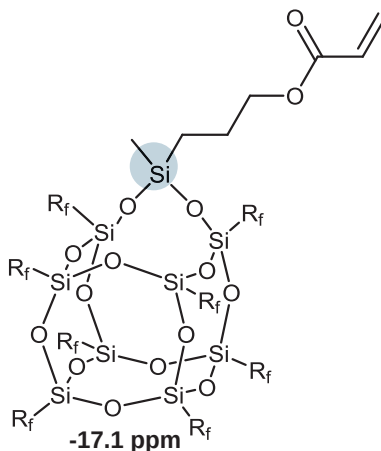
-32.1 ppm



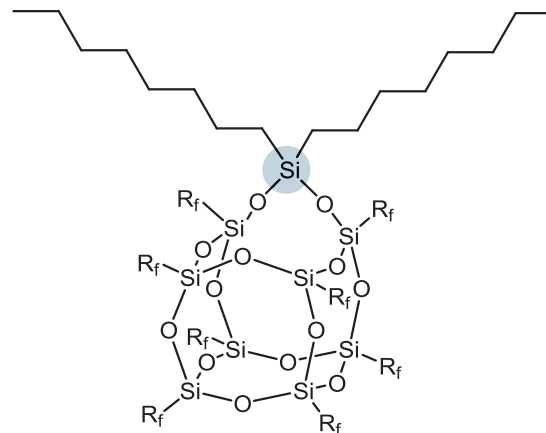
-17.8 ppm



-45.5 ppm



-17.1 ppm



-17.9 ppm

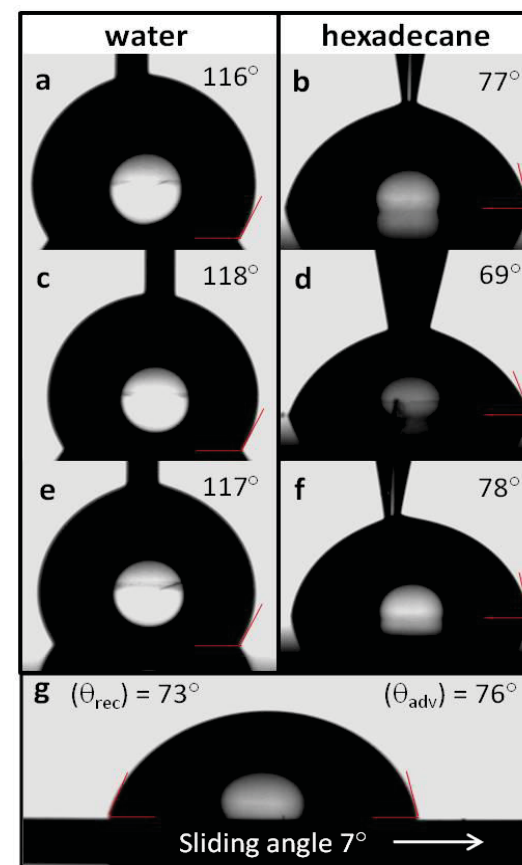
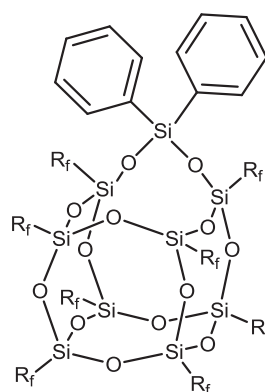
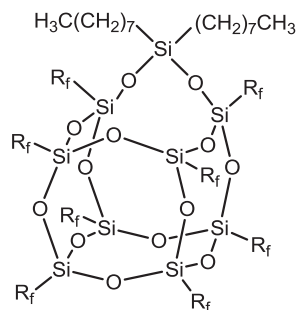
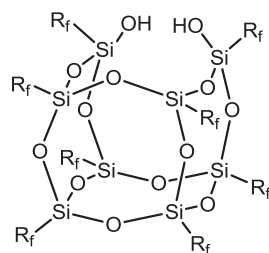
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Ramirez, S. M.; Diaz, Y. J.; Campos, R.; Stone, R.T.; Haddad, T.S.; Mabry, J.M., *J. Am. Chem. Soc.*, 2011, 133, 20084.



Contact Angle Measurements

- Non-wetting surfaces can be developed by a combination of three parameters
 - Chemical functionality (high fluorine content)
 - Roughness (micro- and nanoscale)
 - Surface Geometry (re-entrant curvature)
- What type of influence will functional groups have on F-POSS surface properties?*
- Solvent impact?*

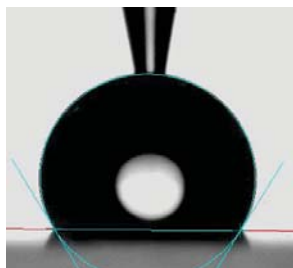


Static contact angles of Si wafer surfaces coated with compounds **disilanol** (a) and (b), **dioctyl** (c) and (d), and **diphenyl** (e) and (f). Image of hexadecane droplet ($10\mu\text{L}$) rolling off surface coated with compound **diphenyl** (g).

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Dynamic Contact Angle Measurements



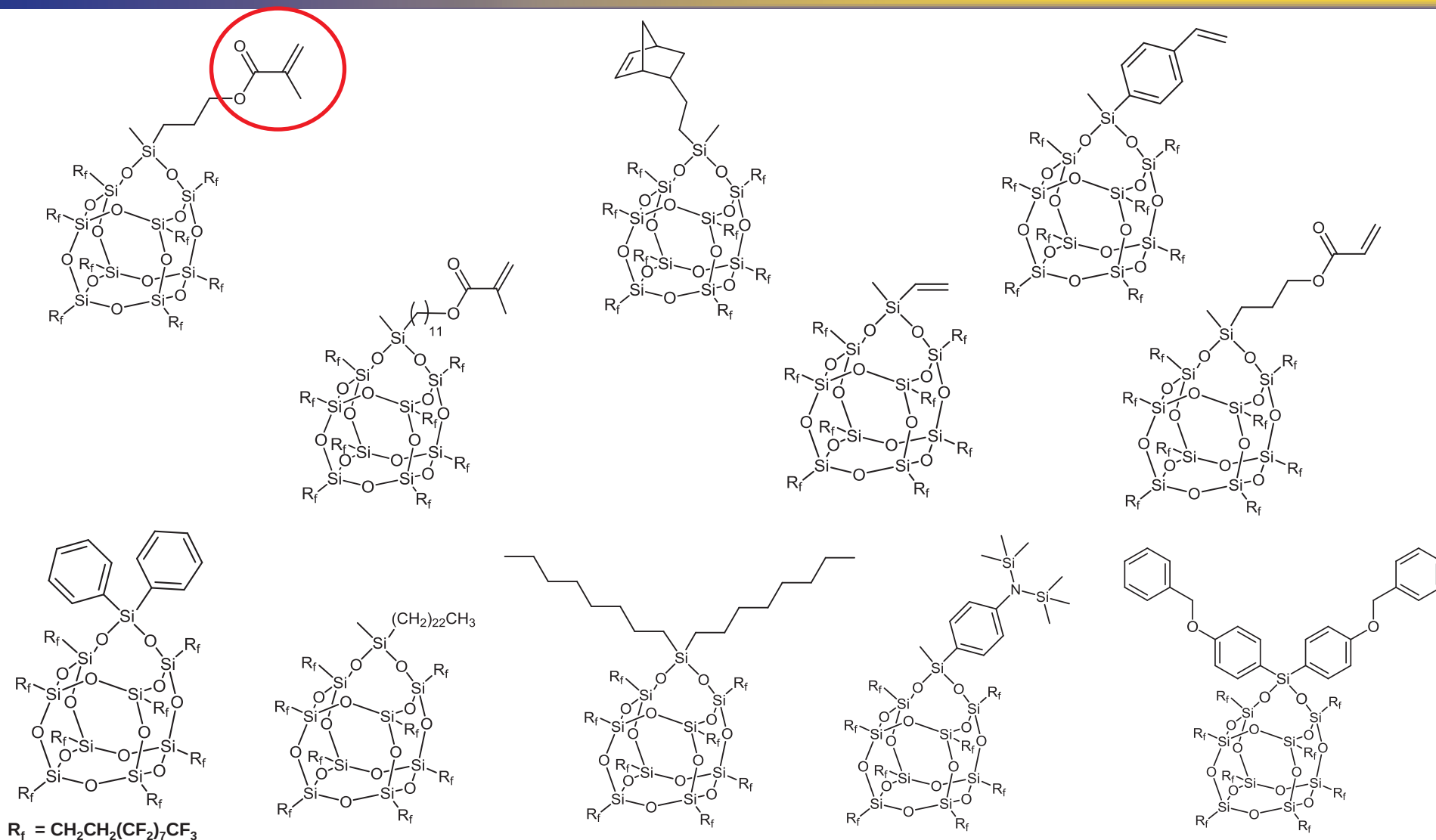
<i>Functional Group on F-POSS</i>	<i>water</i>		<i>hexadecane</i>	
	(θ_{adv})	(θ_{rec})	(θ_{adv})	(θ_{rec})
F-POSS*	$124 \pm 0.5^\circ$	$109.6 \pm 0.7^\circ$	$79.1 \pm 0.4^\circ$	$65.1 \pm 0.5^\circ$
Si-(OH) ₂	$116.8 \pm 0.4^\circ$	$111 \pm 0.6^\circ$	$77.4 \pm 0.4^\circ$	$74.4 \pm 0.8^\circ$
Si-(CH ₃)(CH=CH ₂)	$116.2 \pm 0.4^\circ$	$100.6 \pm 0.8^\circ$	$78.4 \pm 0.3^\circ$	$70.6 \pm 2.3^\circ$
Si((CH ₃)((CH ₂) ₃ OC(O)CCH=CH ₂)	$118.2 \pm 1.0^\circ$	$90.6 \pm 1.0^\circ$	$76.8 \pm 0.3^\circ$	$64.8 \pm 1.0^\circ$
Si-(CH ₃)((CH ₂) ₃ OC(O)C(CH ₃)=CH ₂)	$117.1 \pm 0.6^\circ$	$93.8 \pm 1.5^\circ$	$78.1 \pm 0.4^\circ$	$63.0 \pm 1.2^\circ$
Si-(CH ₃)((CH ₂) ₂₂ CH ₃)	$117.9 \pm 0.4^\circ$	$96.9 \pm 1.9^\circ$	$78.0 \pm 0.4^\circ$	$16.2 \pm 5.5^\circ$
Si-(C ₆ H ₅) ₂	$116.2 \pm 0.4^\circ$	$110.5 \pm 0.5^\circ$	$76.0 \pm 0.8^\circ$	$73.2 \pm 0.4^\circ$
Si-((CH ₂) ₇ CH ₃) ₂	$117.9 \pm 0.5^\circ$	$95.5 \pm 0.4^\circ$	$69.1 \pm 1.2^\circ$	$23.1 \pm 1.2^\circ$

Samples (10 mg/mL) were spin casted on oxygen-plasma cleaned Si wafers at 900 rpm for 30 seconds. Contact angle measurements were run in triplicate. Surface roughness < 5nm (AFM and Optical Profilometry).

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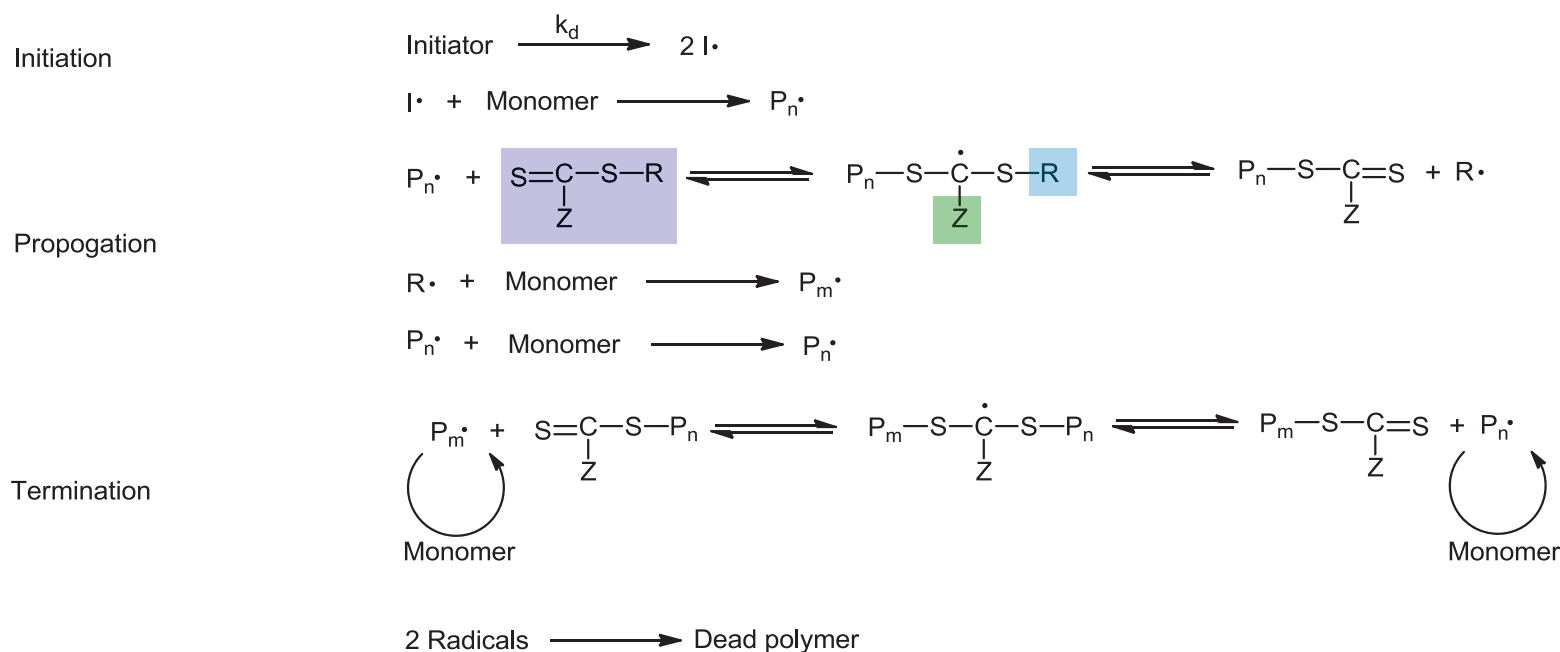
F-POSS Structures Synthesized



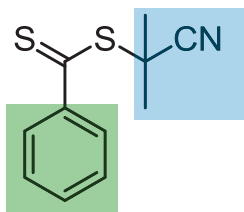
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Reversible Addition-Fragmentation chain Transfer (RAFT) polymerization



Chain Transfer Agent



RAFT Polymerization

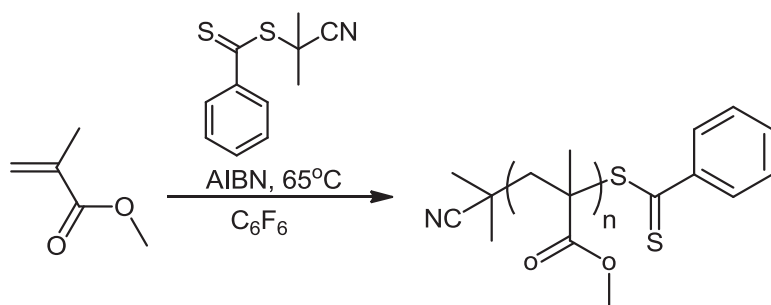
- Controlled polymerization
- Allows for block copolymers
- Tune molecular weight

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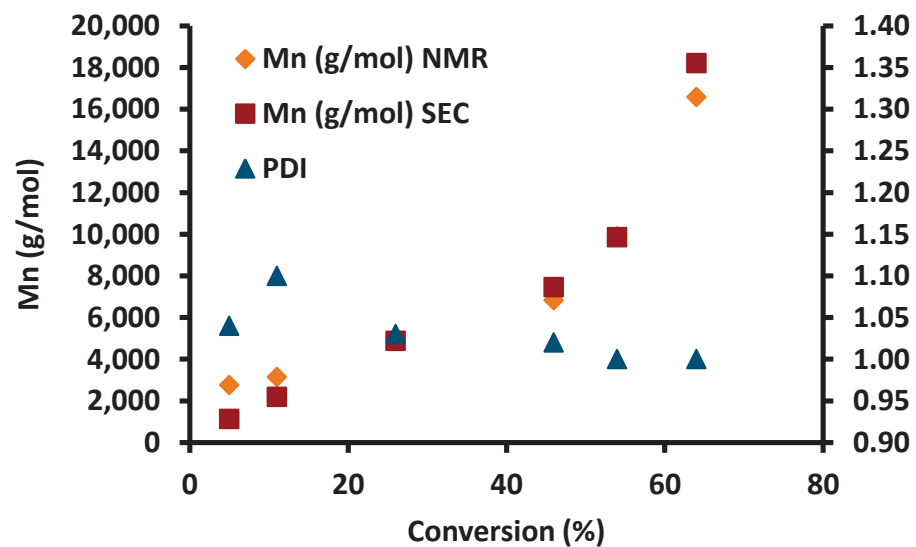
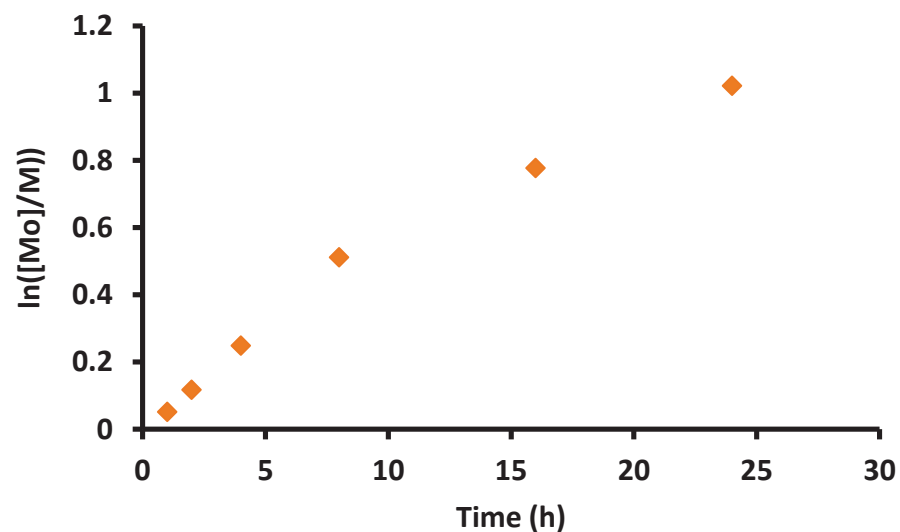
Chiefari, J.; Chong, Y. K.; Ercole, F.; Krstina, J.; Jeffery, J.; Le, T. P. T.; Mayadunne, R. T. A.; Meijs, G. F.; Moad, C. L.; Moad, G.; Rizzardo, E.; Thang, S. H., *Macromolecules* 1998, 31, 5559–5562.
Moad, G.; Biccocchi, E.; Chen, M.; Chiefari, J.; Guerrero-Sanchez, C.; Haeussler, M.; Houshyar, S.; Keddie, D.; Rizzardo, E.; Thang, S. H.; Tsanakisidis, J., *ACS Symp. Ser.* 2012, 1100, 243-258.



RAFT polymerization of MMA in C_6F_6



- Testing RAFT in fluorinated solvent
- RAFT polymerization proceeds in C_6F_6
- Best control in first 10 hours

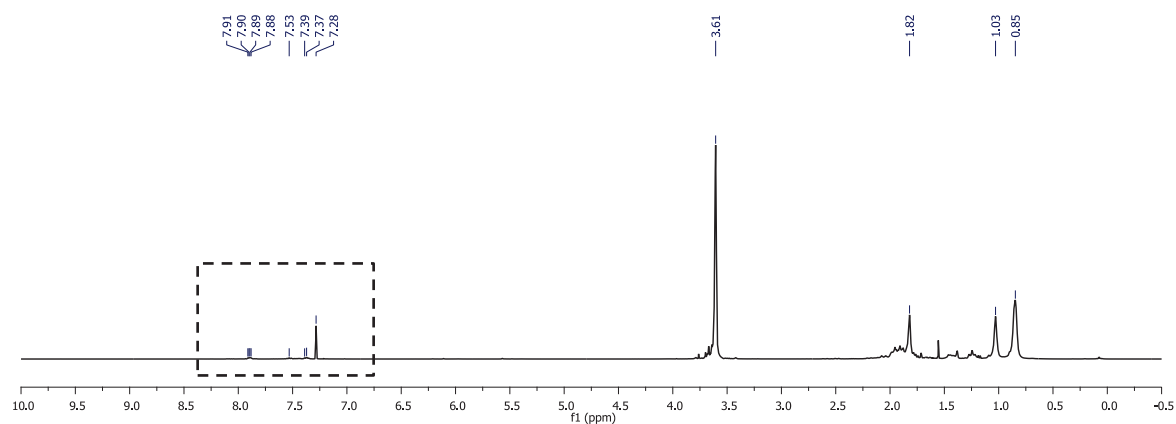
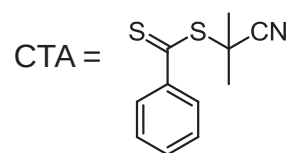
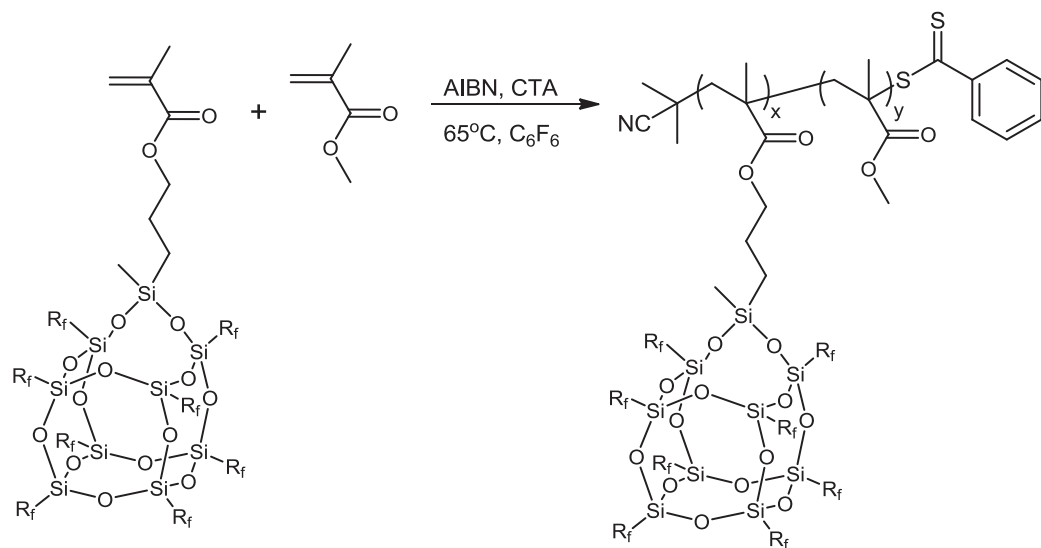


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SEC MALLS: RI and LS detector (Wyatt), 1.0 mL/min, 30 min, THF.



RAFT copolymerization of P(F-POSS-MA)-co-PMMA



$R_f = \text{CH}_2\text{CH}_2(\text{CF}_2)_7\text{CF}_3$

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¹H NMR in CDCl₃



RAFT copolymerization of P(F-POSS-MA)-co-PMMA



F-POSS		M _w	Conv.	water		hexadecane	
wt %	(g/mol)	PDI	%	(θ _{adv})	(θ _{rec})	(θ _{adv})	(θ _{rec})
F-POSS-MMA				117.1 ± 0.6°	93.8 ± 1.5°	78.1 ± 0.4°	63.0 ± 1.2°
0	58,100	1.05	73	77.8 ± 1.3°	57.8 ± 2.5°	wetted	wetted
1	58,700	1.08	72	109.2 ± 2.4°	61.5 ± 1.9°	67.8° ± 1.4	wetted
5	23,000	1.01	30	117.8 ±1.6°	95.7 ± 5.9°	76.7 ± 1.1°	68.8 ± 1.9°
10	26,600	1.01	29	118.2 ± 1.4°	101.1 ±2.5°	77.2 ± 0.4°	69.5 ± 2.1°
25	37,700	1.03	41	120.8 ± 97.0°	97.0 ± 2.4°	82.9 ± 0.4°	74.6 ± 2.0°

SEC-MALLS conditions: 25°C, flow rate (1 mL/min), solvent (Asahiklin-225 [mixture of dichloropentafluoropropanes]), concentration measured with RI detector. Contact angle conditions: polymer solutions (20 mg/mL) were spun cast on SiO₂ wafers at 900 rpm.

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Isemura, T.; Kakita, R.; Kawahara, K., *Journal of Chromatography A* 2004, 1026, 109-1196.

Wesdemiotis, C.; Pingitore, F.; Polce, M. J.; Russell, V. M.; Kim, Y.; Kausch, C. M.; Connors, T. H.; Medsker, R. E.; Thomas, R. R., *Macromolecules* 2006, 39, 8369-8378.

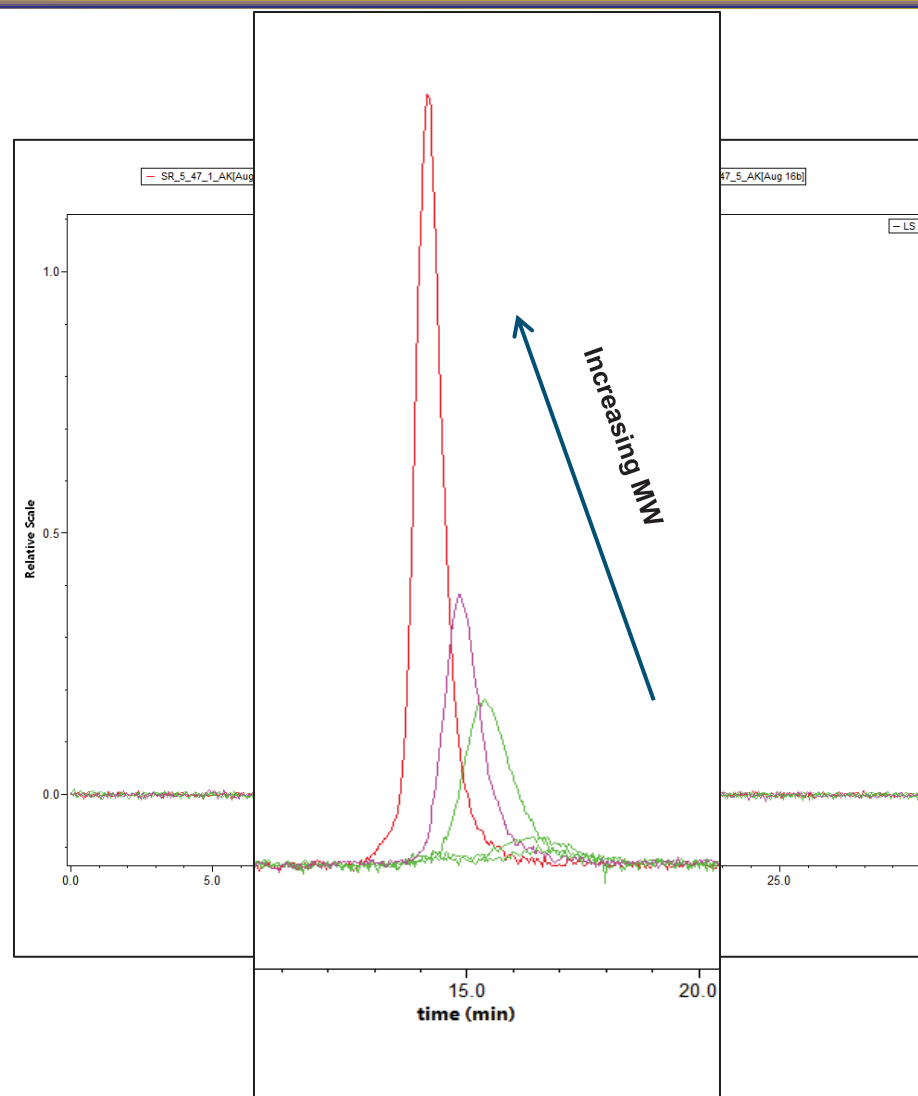


RAFT copolymerization of P(F-POSS-MA)-co-PMMA



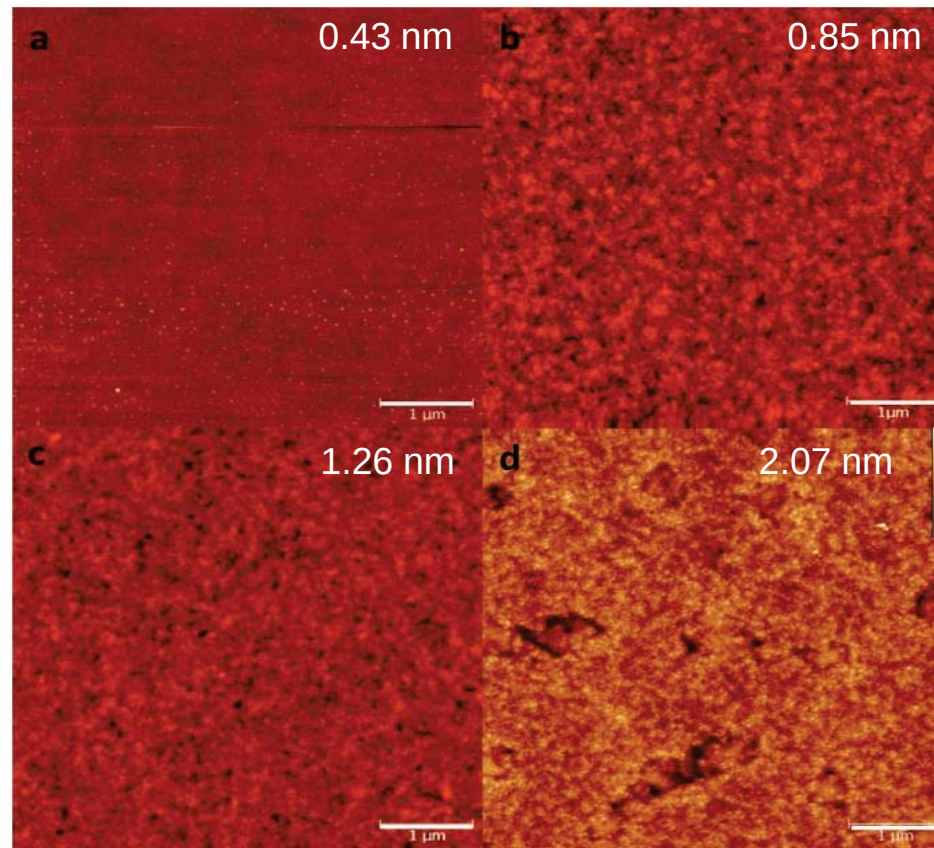
10% F-POSS	M_n		Conv.
Time (hr)	(g/mol)	PDI	%.
1	4100	2.2	8
2	4,700	1.2	16
4	11,300	1.04	28
8	26,600	1.03	51

- **Determining impact of F-POSS on polymerization conditions**
 - No homopolymerization possible
 - Polymerization difficult above 50 wt % F-POSS-MMA loading





AFM of P(F-POSS-MA)-co-PMMA



AFM image of spun cast films of a) 1 wt. % b) 5 wt. %. c) 10 wt. % and d) 25 wt.% F-POSS copolymer on SiO_2 from a 10 mg/mL concentrated solution in Asahiklin-225 at 900 rpm. Each image is shown with a z-scale of 0–10 nm. Top corner of each image root mean squared (rms) surface roughness.

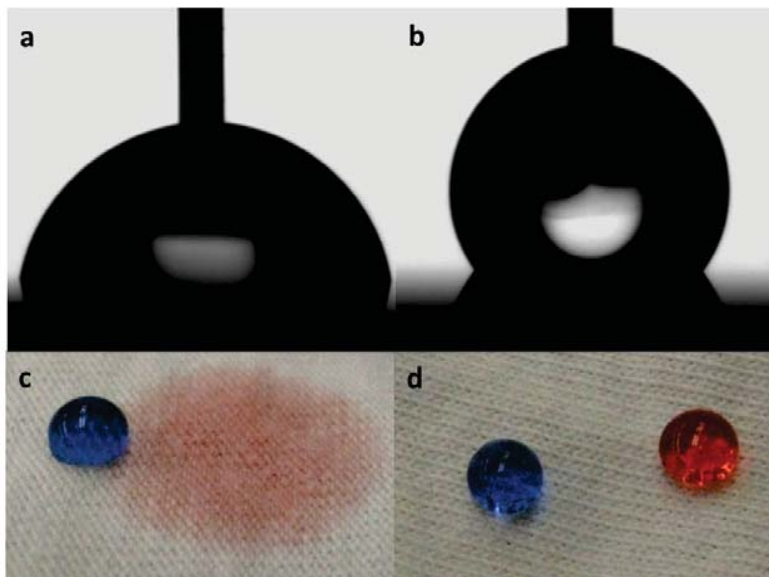
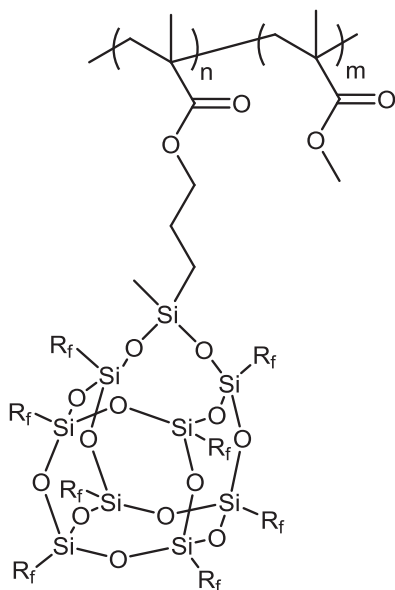
Distribution A: Approved for public release; distribution unlimited



PMMA Copolymerization Summary



- Copolymerizations produced F-POSS based copolymers.
- Polymerization have trouble at higher F-POSS monomer feed ratios and are more controlled at lower conversion with RAFT initiator.
- Can we make homopolymer?



Static contact angle of a water droplet on a) 0 wt.% F-POSS copolymer or b) 25 wt.% F-POSS copolymer. Water (blue) and hexadecane (red) droplets on cotton fabric coated with c) 0 wt.% F-POSS copolymer and d) 25 wt. % F-POSS copolymer from 1% solution in Asahiklin-225.

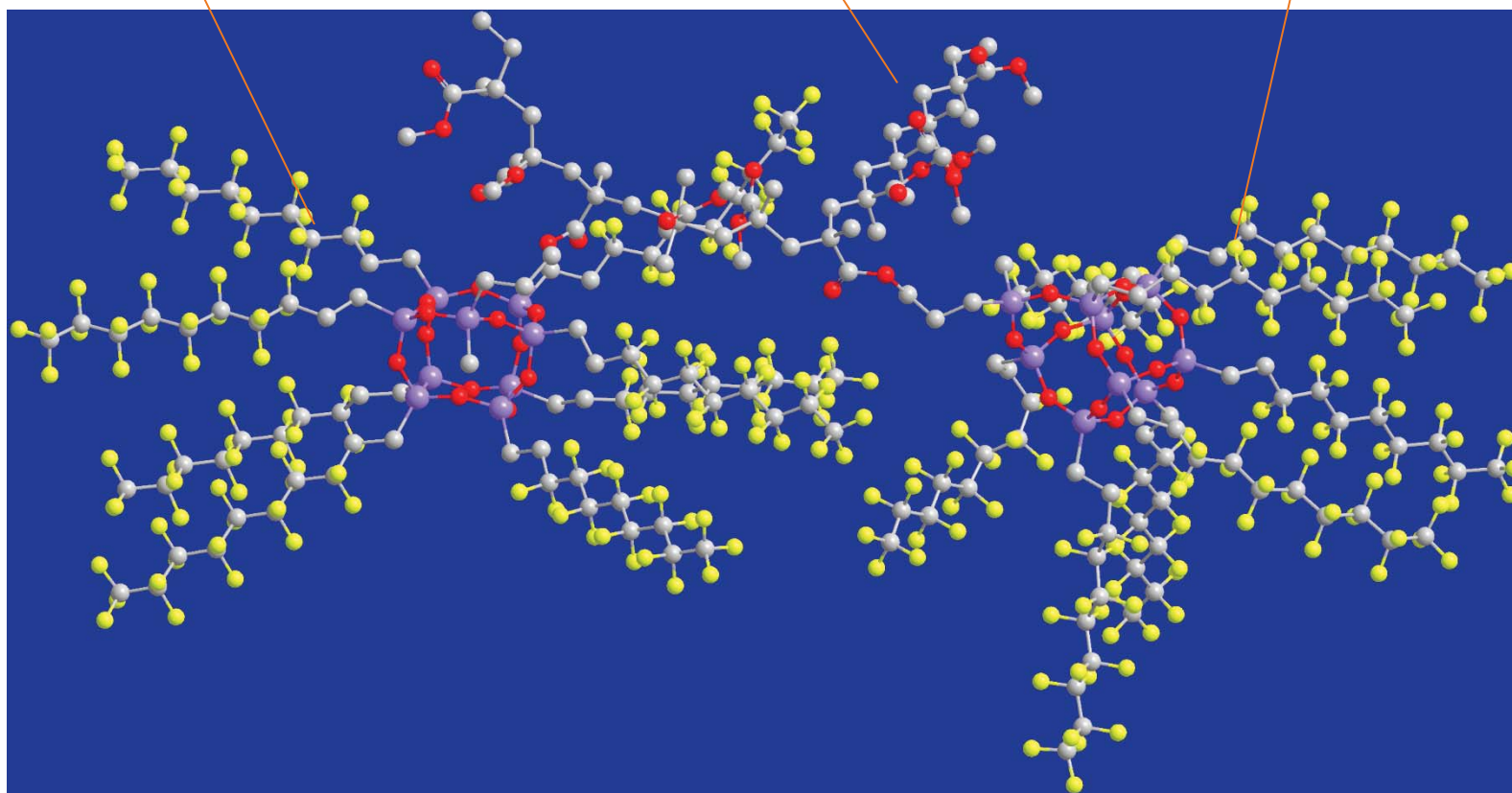


Is it crowded in here?

F-POSS-MA

PMMA backbone (10 rpu)

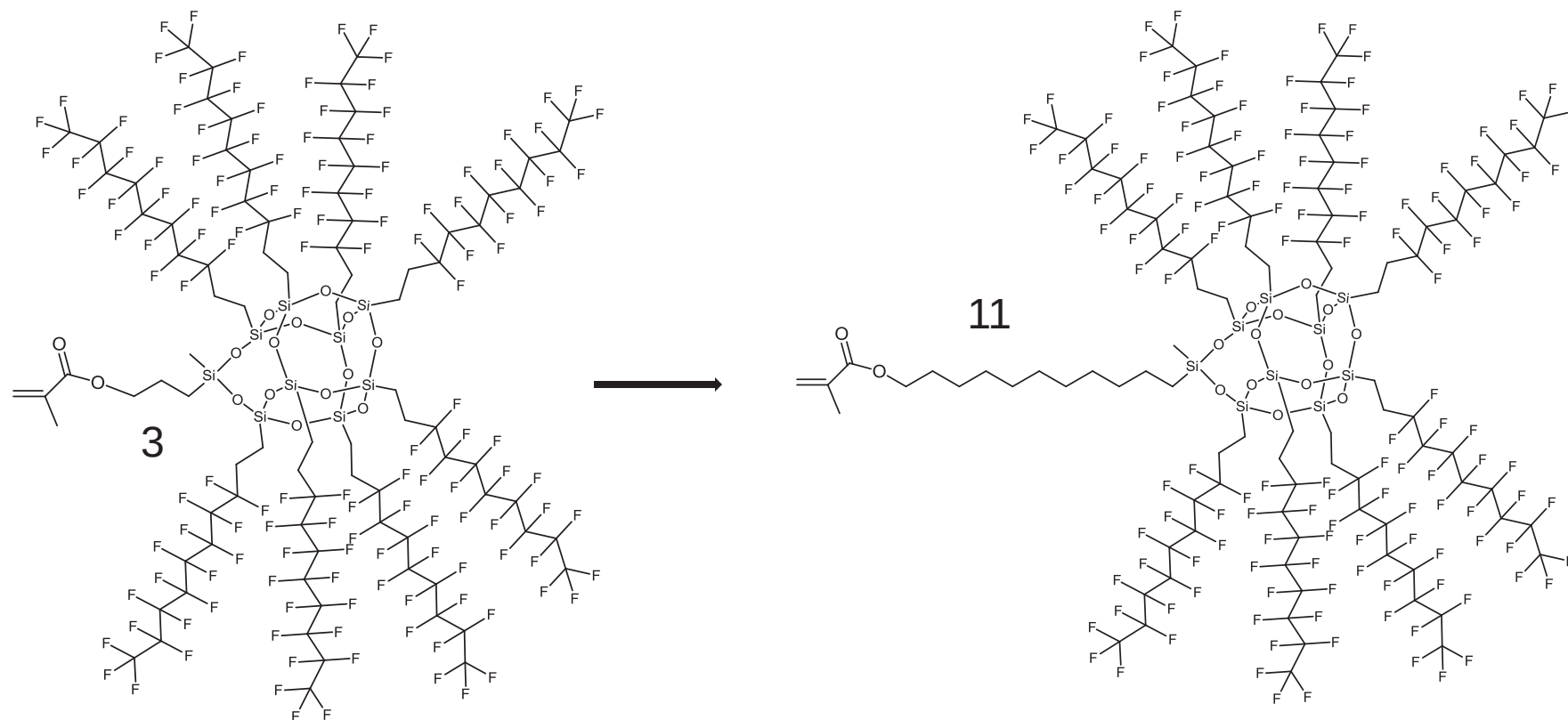
F-POSS-MA



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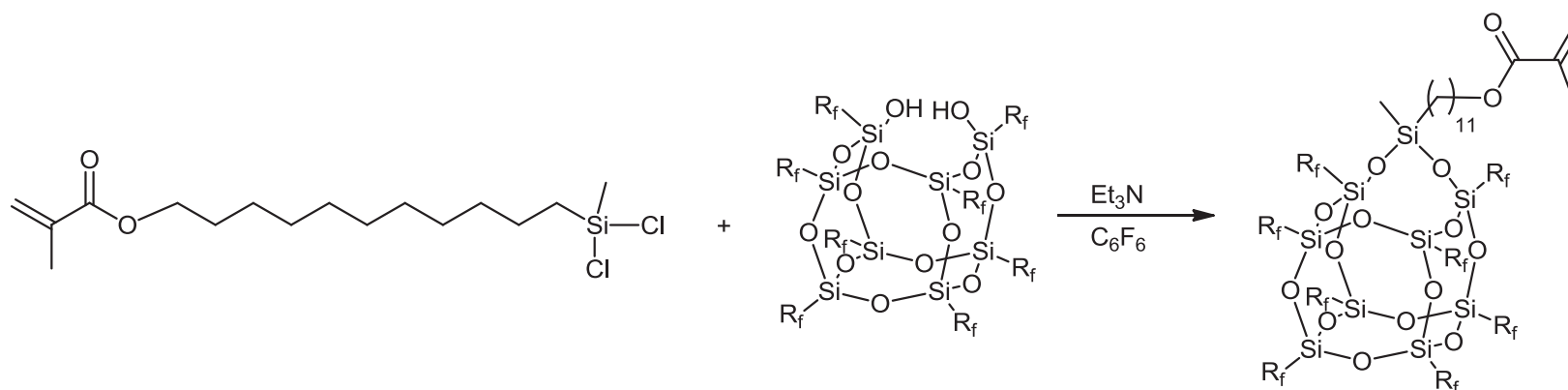
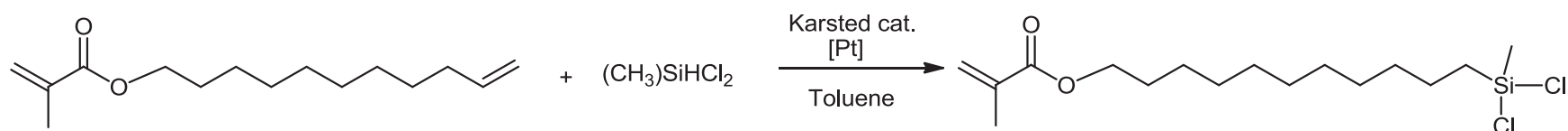
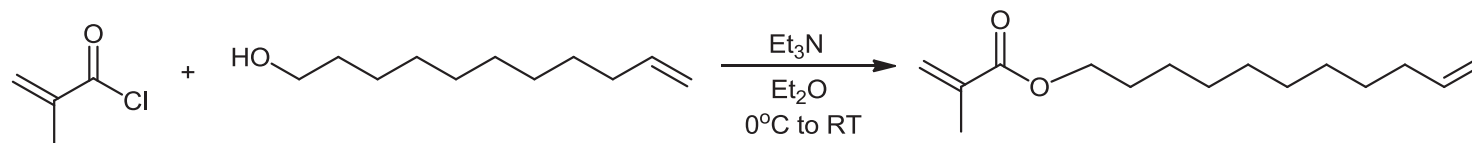


Extend the Chain



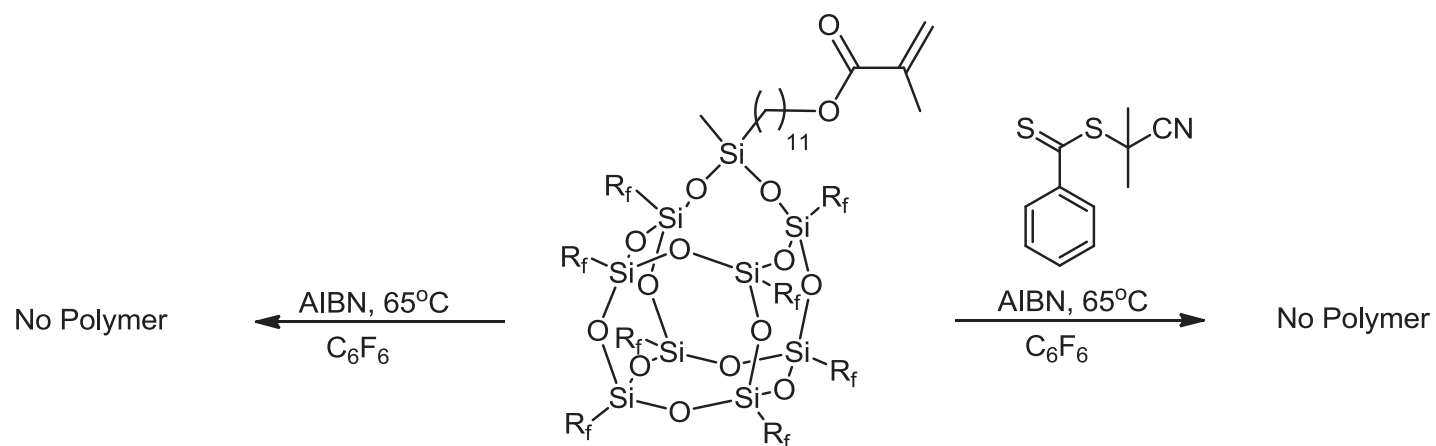


Long Chain Monomer Synthesis





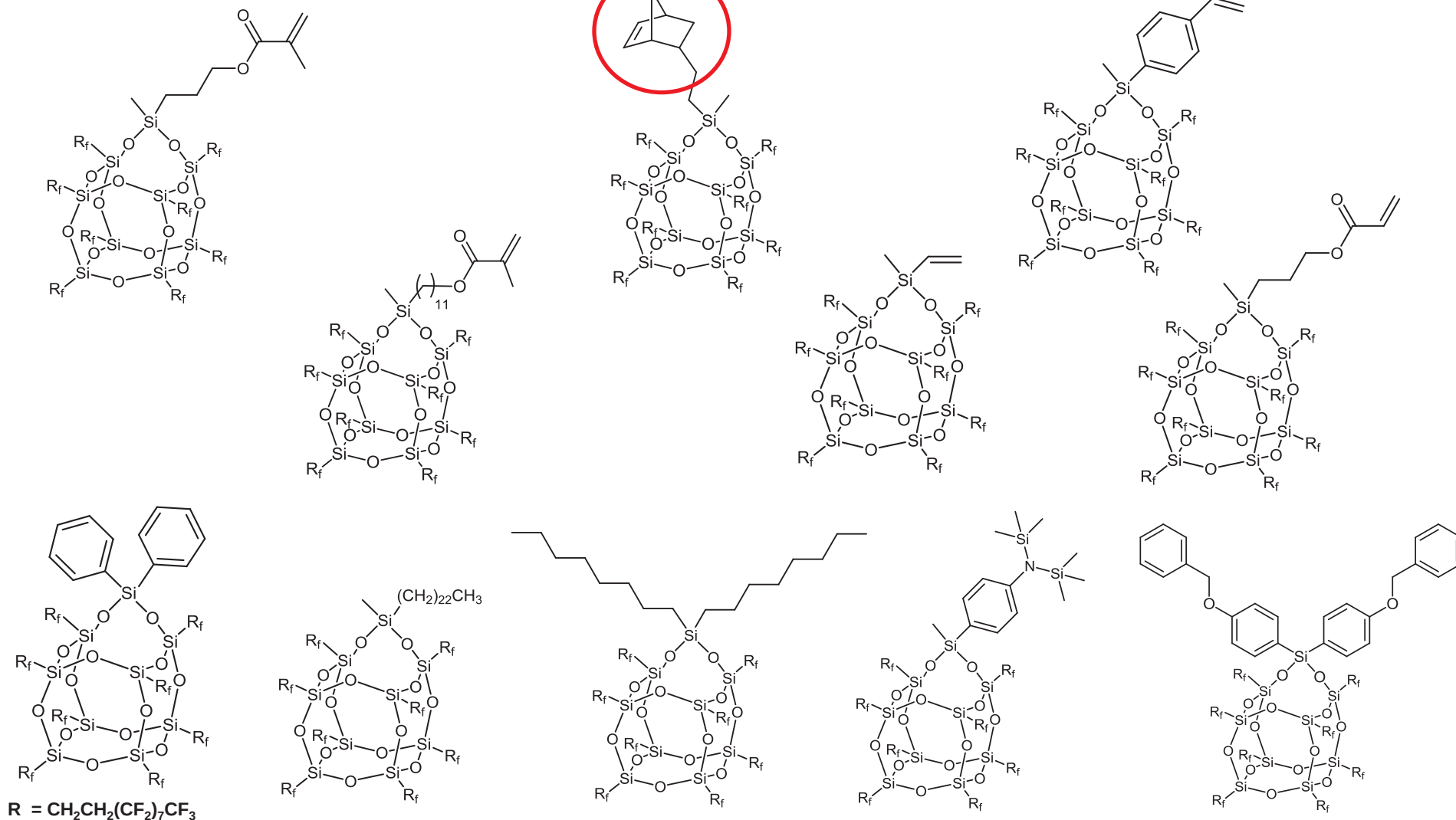
Free Radical Polymerization



- No polymerization



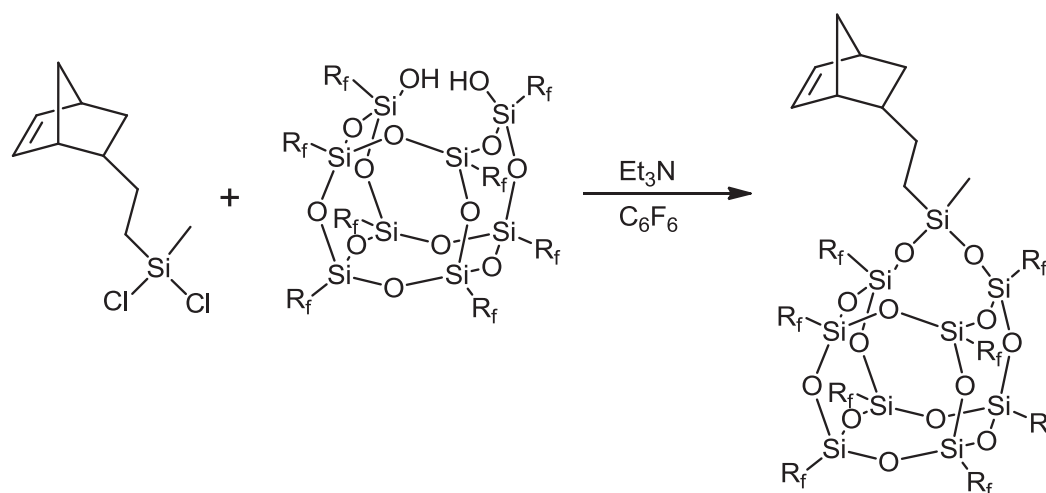
F-POSS Structures Synthesized



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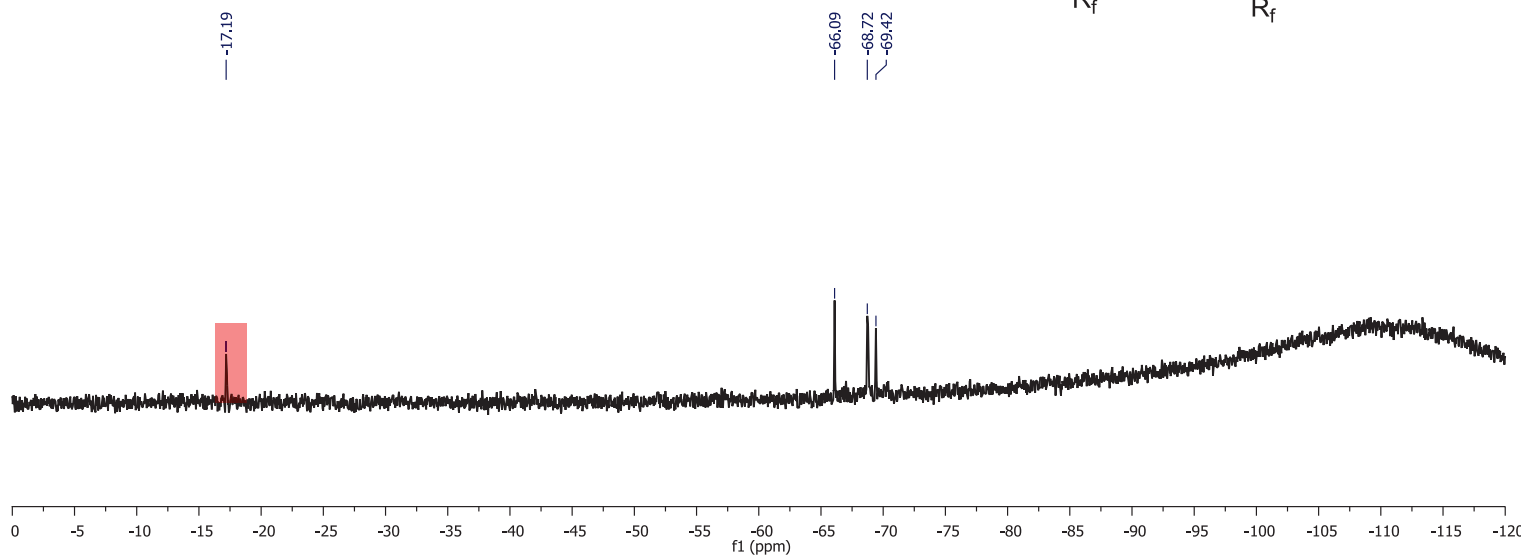
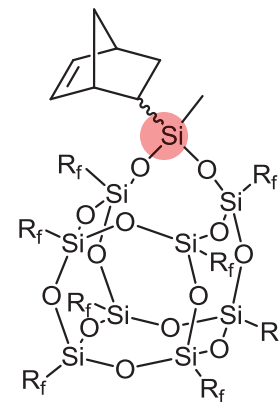
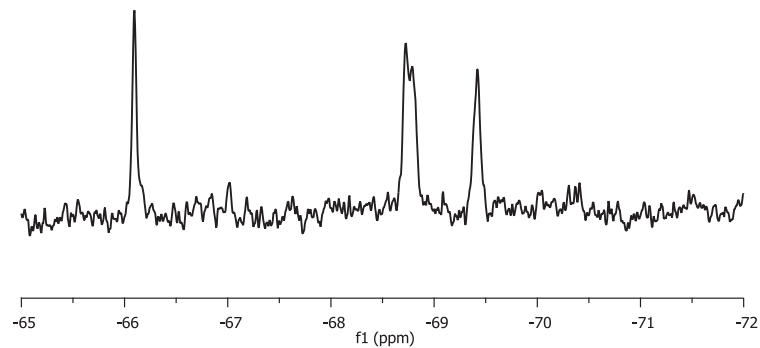
Norbornene Synthesis



- Edge capping reactions typically have 52% yield
- Main side product is starting material (recycled)
- Disilanol can revert back to closed cage during reaction
- Norbornene functionalized F-POSS for ring opening metathesis polymerization (ROMP)



^{29}Si NMR

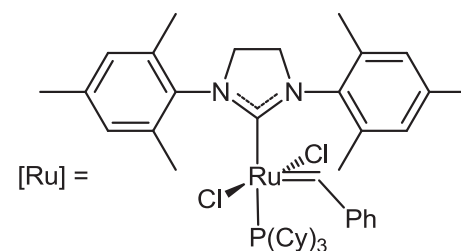
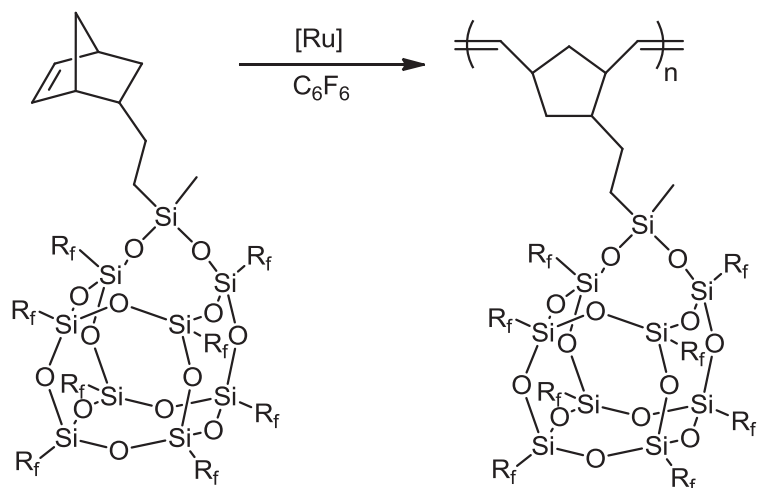


NMR: $\text{CDCl}_3/\text{C}_6\text{F}_6$

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ROMP (Norbornene)



Grubb's 2nd generation catalyst
(soluble in hexafluorobenzene)

- Polymerization

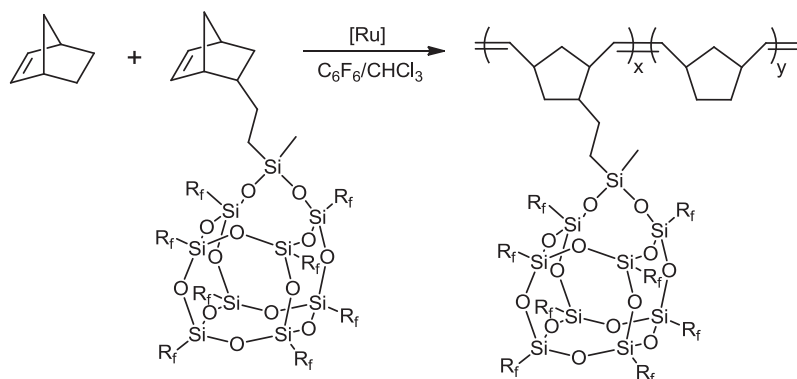
- Multiple polymerization in hexafluorobenzene
- 100:1, 50:1, 25:1 [monomer:catalyst]
- Reaction of 30 minutes (monitored by NMR)
- Higher monomer:catalyst ratios yield insoluble polymers
- Low T_g polymers ($\sim 5^\circ\text{C}$ at $10^\circ\text{C}/\text{min}$ ramp rate) [polynorbornene $\sim 35\text{-}60^\circ\text{C}$]
- Need a method to determine molecular weight

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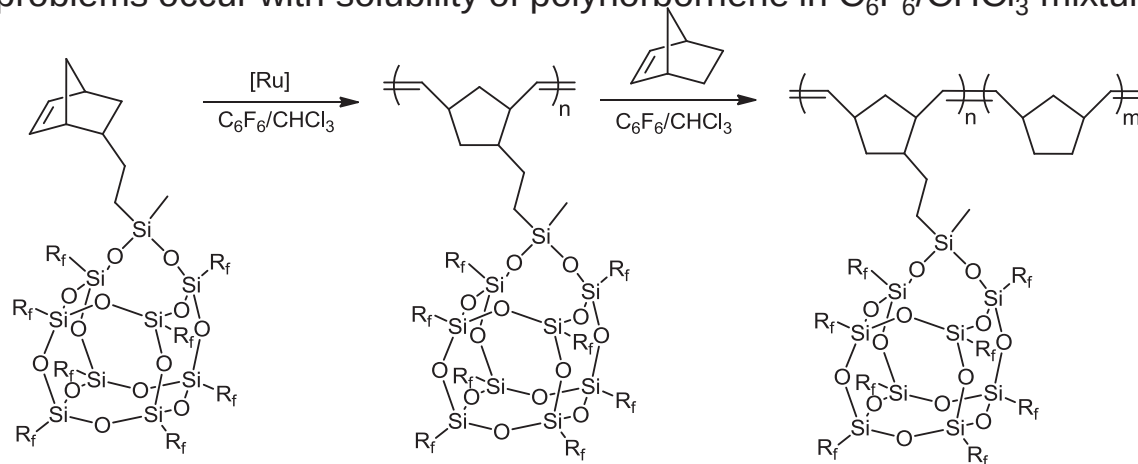


ROMP (Copolymerization)

Two Approaches



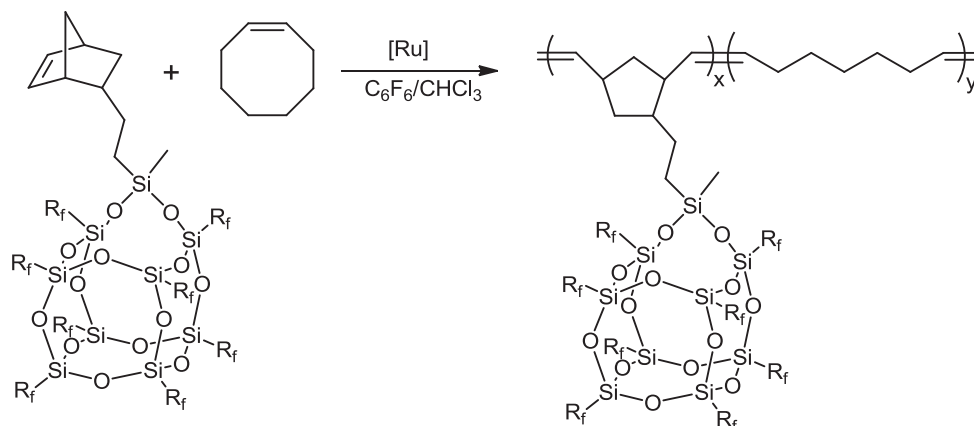
Random copolymer – problems occur with solubility of polynorbornene in $C_6F_6/CHCl_3$ mixture.



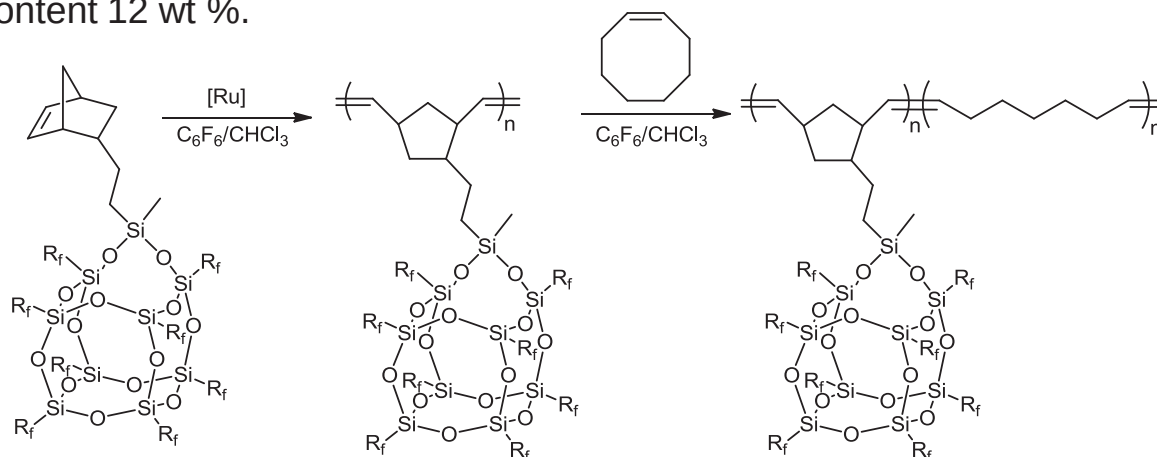
Block copolymers – keeping everything soluble remains a challenge here as well.



ROMP (Cyclooctene)



Random copolymer – resulting polymers are soluble cyclooctene solvents (chloroform, THF, etc...) F-POSS content 12 wt %.



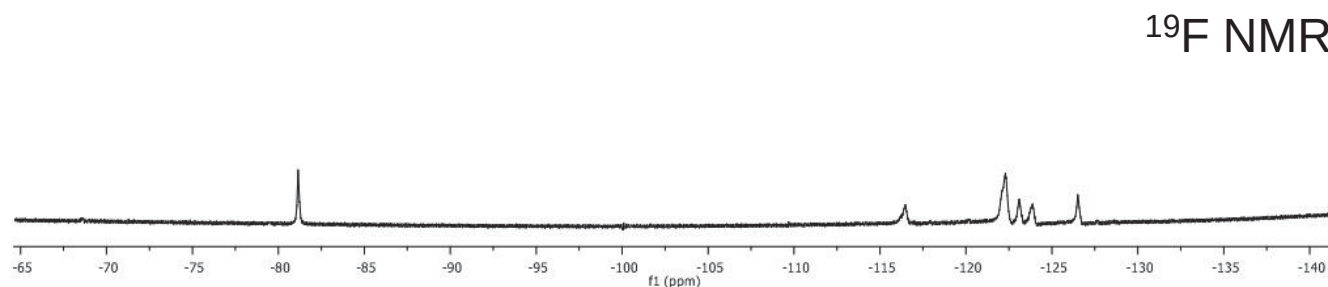
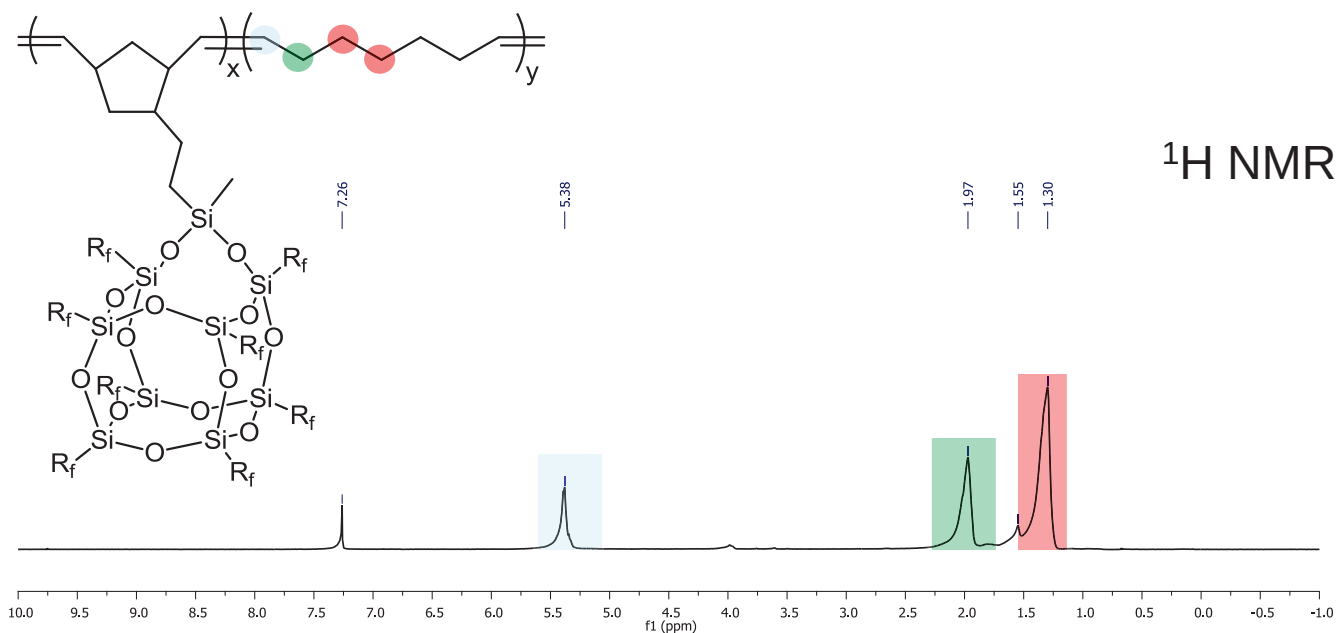
Block copolymers – resulting polymer is insoluble, possibly due to high molecular weight conversion F-POSS content 12 wt %.

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Liu, C.; Chun, S. B.; Zheng, L.; Haley, E.; Coughlin, E. B.; Mather, P. T., *Macromolecules* 2002, 35, 9868-9874. Alonso-Villanueva, J.; Cuevas, J. M.; Laza, J. M.; Vilas, J. L.; Leon, L. M., *Journal of Applied Polymer Science* 2010, 115, 2440-2447. Alonso-Villanueva, J.; Rodriguez, M.; Vilas, J. L.; Laza, J. M.; Leon, L. M., *Journal of Macromolecular Science, Part A: Pure and Applied Chemistry* 2010, 47, 1130-1134.



NMR of Copolymer



Polymer was precipitated in methanol, dissolved, and precipitated into asahiklin-225 before NMR.



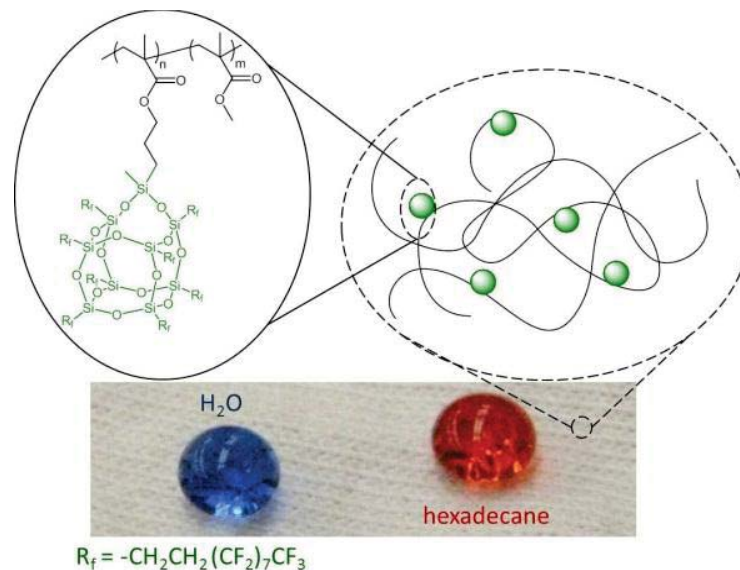
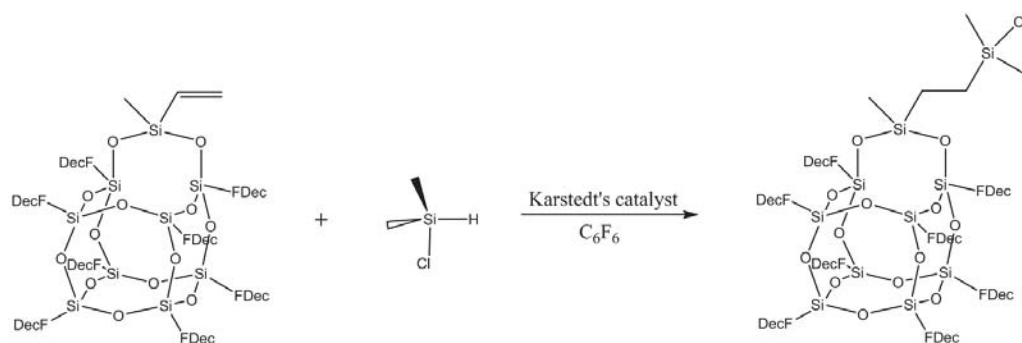
CDCl_3

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Summary

- RAFT copolymerizations were shown to be controlled and highly reproducible.
- ROMP polymerization works well. Work needs to be done with catalyst choice, solvent, and other reaction condition.
- F-POSS compounds have a near limitless potential in producing a variety of new hydrophobic, oleophobic, or ominiphobic polymer composites.
 - Reaction mechanisms, polymer composites, block copolymers, etc....





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Dr. Josiah Reams	Ms. Dana Pinson
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UT Dallas:

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Mr. Raymond Compos*

^ξSummer coop/student (undergraduate)

*Former group member

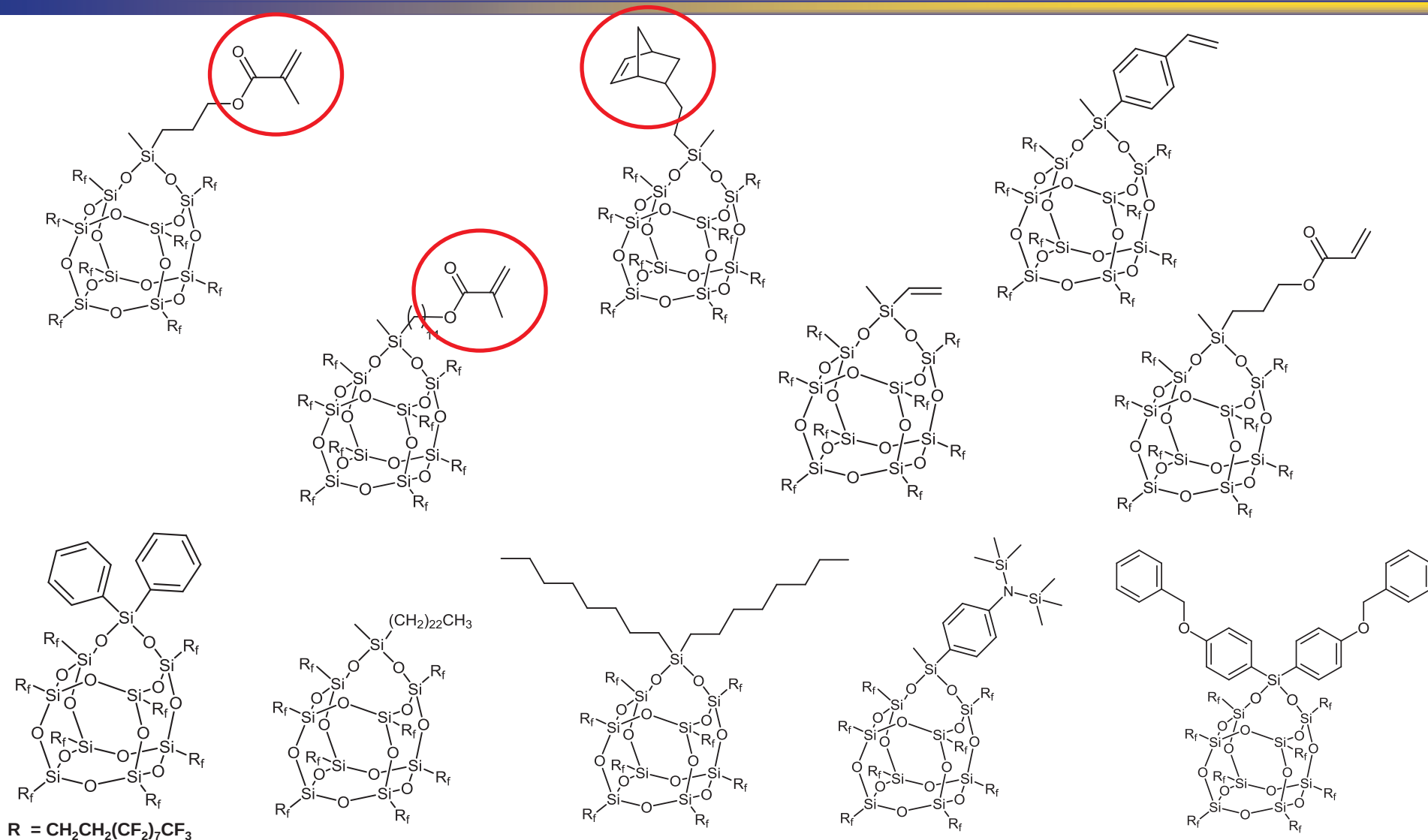
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F-POSS Structures Synthesized



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